

Express Mail No. ER534274197US
Attorney Docket No.: AM-5852.D1

THE UNITED STATES PATENT AND TRADEMARK OFFICE

IN RE APPLICATION OF: Scott Fuller et al.

§ GROUP ART UNIT: 1756
§ (Parent Application)

SERIAL NO.: 10/758,827

§
§ EXAMINER: N. M. Barreca
§ (Parent Application)

FILED: January 15, 2004

§
§ Attorney Docket No.:
§ AM-5852.D1

FOR: METHOD OF INCREASING THE SHELF LIFE
OF A PHOTOMASK SUBSTRATE

Date: February 18, 2004

**INFORMATION DISCLOSURE STATEMENT
UNDER 37 CFR § 1.97(b)(1)**

**Hon. Commissioner for Patents
P.O. Box 1450
Alexandria, Virginia 22313-1450**

Sir:

In accordance with 37 CFR § 1.97(b)(1), applicants hereby request consideration of this Information Disclosure Statement. This Information Disclosure Statement is being submitted within three (3) months of the filing date of the subject application. Applicants are providing herewith a copy of each document cited on the attached Form PTO-1449.

CERTIFICATE OF MAILING UNDER 37 CFR § 1.10

I hereby certify that this paper is being deposited with the U.S. Postal Service on the date shown below with sufficient postage as U.S. EXPRESS MAIL NO. ER534274197US in an envelope addressed to: Mail Stop DD, Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450

Date: February 18, 2004

Shirley L. Church, Reg. No. 31,858

The submission of this Information Disclosure Statement and Form PTO-1449 is not an admission that the art cited is "prior art" with respect to the present invention, nor is it a representation that no better art exists. Applicants hereby reserve the right to swear behind or otherwise disprove any alleged "prior" nature of any art cited should the facts support and the situation warrant such an action.

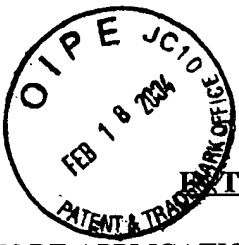
If the Examiner has any questions, she is respectfully requested to contact the undersigned attorney at the telephone number set forth below.

Respectfully submitted,



Shirley L. Church
Registration No. 31,858
Attorney for Applicants
(650) 473-9700

Correspondence Address:
Patent Counsel
Applied Materials, Inc.
P.O. Box 450-A
Santa Clara, California 95052



02-20-04

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**INFORMATION DISCLOSURE STATEMENT
TRANSMITTAL LETTER**

**Hon. Commissioner for Patents
P.O. Box 1450
Alexandria, Virginia 22313-1450**

Sir:

Applicants are submitting the subject Information Disclosure Statement under 37 CFR § 1.97(b)(1). This Information Disclosure Statement is being submitted within three (3) months of the filing date of the subject application.

CERTIFICATE OF MAILING UNDER 37 CFR § 1.10

I hereby certify that this paper is being deposited with the U.S. Postal Service on the date shown below with sufficient postage as U.S. EXPRESS MAIL NO. ER534274197US in an envelope addressed to: Mail Stop DD, Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450.

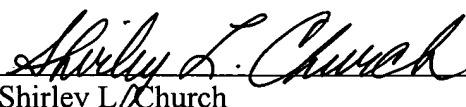
Date: February 18, 2004

Shirley L. Church
Shirley L. Church, Reg. No. 31,858

Applicants do not believe that any fee is due in connection with the filing of this Information Disclosure Statement under 37 CFR § 1.97(b)(1). However, in the event that any additional fee is due, the Commissioner is hereby authorized to charge Deposit Account No. 50-1512 of Shirley L. Church, Sunnyvale, California, in the amount of such fee.

This transmittal letter is submitted in duplicate for accounting purposes.

Respectfully submitted,


Shirley L. Church
Registration No. 31,858
Attorney for Applicants

Correspondence Address:
Patent Counsel
Applied Materials, Inc.
P.O. Box 450-A
Santa Clara, California 95052

FORM PTO-1449
(Equivalent)

U.S. Department of Commerce
Patent and Trademark Office

U.S. Application Serial No.
10/758,827

Atty. Docket No.
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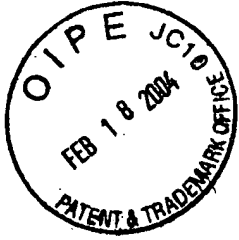
INFORMATION DISCLOSURE
STATEMENT BY APPLICANT

Scott Fuller et al.
Applicants

(Use several sheets if necessary)

January 15, 2004
Filing Date

1756
Group



U. S. PATENT DOCUMENTS

Examiner Initial	Document Number	Issue Date	Name	Class	Subclass	Filing Date If Appropriate
_____	4,102,683	07/25/78	DiPiazza	96	38.4	
_____	4,357,416	11/02/82	Fan	430	302	
_____	5,234,990	08/10/93	Flaim et al. *	524	609	
_____	5,278,010	01/11/94	Day et al.	430	18	
_____	5,554,485	09/10/96	Dichiara et al. *	430	271.1	
_____	5,723,237	03/03/98	Kobayashi et al. *	430	30	
_____	5,879,853	03/09/99	Azuma *	430	166	
_____	5,879,863	03/09/99	Azuma et al.	430	322	
_____	5,935,768	08/10/99	Biche et al. **	430	401	
_____	5,939,236	08/17/99	Pavelchek et al.	430	273.1	
_____	6,048,672	04/11/00	Cameron et al.	430	327	
_____	6,110,638	08/29/00	Masuda et al. **	430	270.1	

Examiner _____ Date Considered _____

Examiner: Initial if citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

* Cited in a Search Report in corresponding PCT Application No. PCT/US02/22609.

** Cited during the prosecution of the parent application, U.S. Application Serial No. 09/912,116.

U. S. PATENT DOCUMENTS

<u>Examiner Initial</u>	<u>Document Number</u>	<u>Issue Date</u>	<u>Name</u>	<u>Class</u>	<u>Subclass</u>	<u>Filing Date If Appropriate</u>
_____	6,156,479	12/05/00	Meador et al.	430	270.1	
_____	6,169,029	01/02/01	Yang **	438	671	
_____	6,183,915	02/06/01	Rolfson **	430	5	
_____	6,316,167	11/13/01	Angelopoulos et al. **	430	313	01/10/00
_____	6,340,553	01/22/02	Oomori et al. **	430	270.1	06/02/00
_____	6,353,209	03/05/02	Schaper et al. **	219	444.1	12/08/99
_____	6,433,348	08/13/02	Abboud et al. **	250	492.2	07/25/00

U. S. PATENT APPLICATION DOCUMENTS

<u>Examiner Initial</u>	<u>Document Number</u>	<u>Publication Date</u>	<u>Name</u>	<u>Class</u>	<u>Subclass</u>	<u>Filing Date</u>
_____	2002/0012876 A1	01/31/02	Angelopolous et al. *	430	271.1	08/17/01
_____	2002/0182514 A1	12/05/02	Montgomery et al. **	430	5	05/03/01

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FOREIGN PATENT DOCUMENTS

<u>Examiner Initial</u>	<u>Document Number</u>	<u>Publication Date</u>	<u>Name</u>	<u>Class</u>	<u>Subclass</u>	<u>Translation (If Appropriate)</u>
_____	EP 0588087	03/23/94	Ogawa et al. *	H01L	21/027	
_____	EP 0905565	03/31/99	Lu et al. *	G03F	7/09	
_____	EP 0987600	03/22/00	Adams et al. *	G03F	7/09	
_____	EP 0989460	03/29/00	Shimomura et al.	G03F	7/004	
_____	EP 1035442	09/13/00	Pavelchek et al. *	G03F	7/09	
_____	EP 1046958	10/25/00	Pawlowski et al. *	G03F	7/11	
_____	GB 2349148	10/25/00	Jung et al.	C07C	69/54	
_____	JP 10048831	02/20/98	Sony Corp.	G03F	007/11	Abstract
_____	JP 10048832	02/20/98	Sony Corp.	G03F	007/11	Abstract
_____	WO 0046643	08/10/00	Smith et al. *	G03F	9/00	
_____	WO 0054105	09/14/00	Foster et al.	G03C	1/492	

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OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, etc.)

_____ * G. Amblard et al., "Diffusion Phenomenon and Loss of Adhesion in Chemically Amplified Negative Resists", *Microelectronic Engineering*, 17, pp. 275-278 (1992).

_____ ** P. Buck et al., "Performance of the ALTA® 3500 scanned-laser mask lithography system", *Proceedings of the SPIE Conference on Photomask and X-Ray Mask Technology V*, Kawasaki, Japan, SPIE Vol. 3412, pp. 67-78 (April 1998).

_____ * K. Katoh et al., "Improvement of Post Exposure Delay Stability of Chemically Amplified Positive Resist", *Proceedings of the SPIE Symposium on Photomask and X-Ray Mask Technology VI*, Yokohama, Japan, SPIE Vol. 3748, pp. 62-68 (Sept 1999).

_____ K. Kemp et al., "Effects of DUV Resist Sensitivities on Lithographic Process Window", *SPIE*, Vol. 3049, pp. 955-962 (1997).

_____ C. A. Mack et al., "Matching Simulation and Experiment for Chemically Amplified Resists", *Proceedings of the SPIE Conference on Optical Microlithography XII*, SPIE Vol. 3679, pp.183-192 (March 1999).

_____ Z. Masnyj et al., "Evaluation of Negative DUV Resist UVN30 for Electron Beam Exposure of NGL Masks", *SPIE*, Vol. 3997, pp. 525-529 (2000).

_____ U. Okoroanyanwu et al., "Impact of Optical Absorption on Process Control for Sub-0.15- μ m Device Patterning Using 193-nm Lithography", *SPIE*, Vol. 3998, pp.781-790 (2000).

_____ * C. P. Soo et al., "Enhancement or Reduction of Catalytic Dissolution Reaction in Chemically Amplified Resists by Substrate Contaminants", *IEEE Transactions on Semiconductor Manufacturing*, Vol. 12, No. 4, pp. 462-469 (Nov 1999).

_____ M. Zuniga et al., "Application of a General Reaction/Diffusion Resist Model to Emerging Materials with Extension to Non-Actinic Exposure", *SPIE*, Vol. 3049, pp. 256-268 (1997).

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